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(54) Title: METHOD FOR USING COMPOSITION COMPRISING CARBOXYLIC ACID ESTER, LITHOGRAPHY COM-
POSITION COMPRISING CARBOXYLIC ACID ESTER, AND METHOD FOR MANUFACTURING RESIST PATTERN

FIGURES

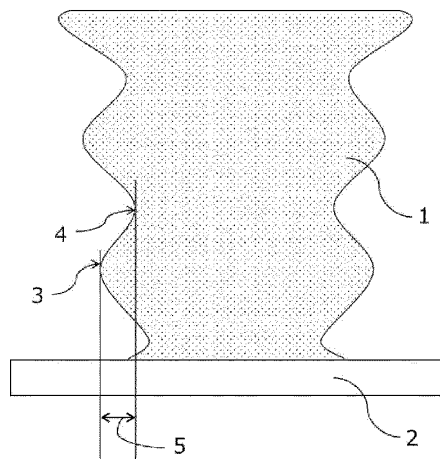


Figure 1

(57) Abstract: A method for using a composition comprising a car-
boxylic acid ester (A) having a certain structure to reduce standing
wave in a lithography process.



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